

J Alexander Liddle

List of Publications by Year in descending order

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235
papers

6,336
citations

76196

40
h-index

82410

72
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242
all docs

242
docs citations

242
times ranked

7319
citing authors

#	ARTICLE	IF	CITATIONS
1	Best practice for improved accuracy: A critical reassessment of vanâ€™t Hoff analysis of melt curves. <i>Biophysical Journal</i> , 2022, 121, 1986-2001.	0.2	3
2	Chromium oxide â€™ A novel sacrificial layer material for MEMS/NEMS and micro/nanofluidic device fabrication. <i>Micro and Nano Engineering</i> , 2022, 16, 100145.	1.4	1
3	Roadmap on emerging hardware and technology for machine learning. <i>Nanotechnology</i> , 2021, 32, 012002.	1.3	104
4	DNA Origami Design: A How-To Tutorial. <i>Journal of Research of the National Institute of Standards and Technology</i> , 2021, 126, .	0.4	7
5	Failure Mechanisms in DNA Self-Assembly: Barriers to Single-Fold Yield. <i>ACS Nano</i> , 2021, 15, 3284-3294.	7.3	12
6	Analysis and uncertainty quantification of DNA fluorescence melt data: Applications of affine transformations. <i>Analytical Biochemistry</i> , 2020, 607, 113773.	1.1	7
7	Revealing thermodynamics of DNA origami folding via affine transformations. <i>Nucleic Acids Research</i> , 2020, 48, 5268-5280.	6.5	13
8	Modeling the Electromagnetic Scattering Characteristics of Carbon Nanotube Composites Characterized by 3-D Tomographic Transmission Electron Microscopy. <i>IEEE Open Journal of Antennas and Propagation</i> , 2020, 1, 142-158.	2.5	5
9	So, You Want to Have a Nanofab? Shared-Use Nanofabrication and Characterization Facilities: Cost-of-Ownership, Toolset, Utilization, and Lessons Learned. <i>Journal of Research of the National Institute of Standards and Technology</i> , 2020, 125, 125009.	0.4	5
10	Nanoscale deformation in polymers revealed by single-molecule super-resolution localizationâ€™orientation microscopy. <i>Materials Horizons</i> , 2019, 6, 817-825.	6.4	21
11	Lowâ€™temperature Growth of Carbon Nanotubes Catalyzed by Sodiumâ€™Based Ingredients. <i>Angewandte Chemie - International Edition</i> , 2019, 58, 9204-9209.	7.2	25
12	Aligned carbon nanotube morphogenesis predicts physical properties of their polymer nanocomposites. <i>Nanoscale</i> , 2019, 11, 16327-16335.	2.8	16
13	The Self-Report Delinquency Scale From the National Longitudinal Study of Adolescent to Adult Health Among At-Risk for Delinquency Youths. <i>Violence and Victims</i> , 2019, 34, 120-135.	0.4	7
14	Subnanometer localization accuracy in widefield optical microscopy. <i>Light: Science and Applications</i> , 2018, 7, 31.	7.7	32
15	Research Update: Electron beam-based metrology after CMOS. <i>APL Materials</i> , 2018, 6, .	2.2	4
16	Nanoparticle Manufacturing â€™ Heterogeneity through Processes to Products. <i>ACS Applied Nano Materials</i> , 2018, 1, 4358-4385.	2.4	68
17	Guiding the Self-Assembly of RecA Proteinfilaments on DNA Scaffolds to Create Rationally Designed Nanostructures. <i>Biophysical Journal</i> , 2017, 112, 515a.	0.2	0
18	Enhanced durability of carbon nanotube grafted hierarchical ceramic microfiber-reinforced epoxy composites. <i>Carbon</i> , 2017, 125, 63-75.	5.4	6

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19	Molecular Precision at Micrometer Length Scales: Hierarchical Assembly of DNA-Protein Nanostructures. <i>ACS Nano</i> , 2017, 11, 6623-6629.	7.3	17
20	Nanolithography Toolbox: Device design at the nanoscale. , 2017, , .		0
21	The Nanolithography Toolbox. <i>Journal of Research of the National Institute of Standards and Technology</i> , 2016, 121, 464.	0.4	54
22	Optical tracking of nanoscale particles in microscale environments. <i>Applied Physics Reviews</i> , 2016, 3, .	5.5	27
23	Trade-off between the Mechanical Strength and Microwave Electrical Properties of Functionalized and Irradiated Carbon Nanotube Sheets. <i>ACS Applied Materials & Interfaces</i> , 2016, 8, 9327-9334.	4.0	12
24	Gravitational Sweep Sedimentation Velocity. <i>Biophysical Journal</i> , 2016, 110, 384a.	0.2	0
25	Multiscale metrologies for process optimization of carbon nanotube polymer composites. <i>Carbon</i> , 2016, 108, 381-393.	5.4	24
26	Giant Surface Conductivity Enhancement in a Carbon Nanotube Composite by Ultraviolet Light Exposure. <i>ACS Applied Materials & Interfaces</i> , 2016, 8, 23230-23235.	4.0	13
27	Assessing fabrication tolerances for a multilevel 2D binary grating for 3D multifocus microscopy. <i>Optics Express</i> , 2016, 24, 9224.	1.7	3
28	Cure temperature influences composite electrical properties by carbon nanotube-rich domain formation. <i>Composites Science and Technology</i> , 2016, 133, 23-32.	3.8	9
29	Optical Fluorescence Microscopy for Spatially Characterizing Electron Transfer across a Solid-Liquid Interface on Heterogeneous Electrodes. <i>MRS Advances</i> , 2016, 1, 2867-2872.	0.5	0
30	Multifocus microscopy with precise color multi-phase diffractive optics applied in functional neuronal imaging. <i>Biomedical Optics Express</i> , 2016, 7, 855.	1.5	47
31	Nanomanufacturing: A Perspective. <i>ACS Nano</i> , 2016, 10, 2995-3014.	7.3	176
32	Variable Field Analytical Ultracentrifugation: II. Gravitational Sweep Sedimentation Velocity. <i>Biophysical Journal</i> , 2016, 110, 103-112.	0.2	25
33	High-Resolution Imaging and Spectroscopy at High Pressure: A Novel Liquid Cell for the Transmission Electron Microscope. <i>Microscopy and Microanalysis</i> , 2015, 21, 1629-1638.	0.2	31
34	New Insights into Sequential Infiltration Synthesis. <i>ECS Transactions</i> , 2015, 69, 147-157.	0.3	35
35	Electromagnetic scattering from multiple Carbon Nanotubes with experimentally determined shapes and distributions. , 2015, , .		1
36	Noncontact conductivity and dielectric measurement for high throughput roll-to-roll nanomanufacturing. <i>Scientific Reports</i> , 2015, 5, 17019.	1.6	13

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37	Staining Block Copolymers using Sequential Infiltration Synthesis for High Contrast Imaging and STEM tomography. <i>Microscopy and Microanalysis</i> , 2015, 21, 611-612.	0.2	7
38	Imaging of Carbon Nanotubes Embedded in Polymer Composites via Low Energy Scanning Electron Microscopy and Scanning Lithium Ion Microscopy. <i>Microscopy and Microanalysis</i> , 2015, 21, 513-514.	0.2	1
39	Rapid Prototyping of Nanofluidic Slits in a Silicone Bilayer. <i>Journal of Research of the National Institute of Standards and Technology</i> , 2015, 120, 252.	0.4	3
40	New insights into subsurface imaging of carbon nanotubes in polymer composites via scanning electron microscopy. <i>Nanotechnology</i> , 2015, 26, 085703.	1.3	15
41	The Evolution of Carbon Nanotube Network Structure in Unidirectional Nanocomposites Resolved by Quantitative Electron Tomography. <i>ACS Nano</i> , 2015, 9, 6050-6058.	7.3	62
42	Characterizing the Three-Dimensional Structure of Block Copolymers via Sequential Infiltration Synthesis and Scanning Transmission Electron Tomography. <i>ACS Nano</i> , 2015, 9, 5333-5347.	7.3	98
43	Metrology of DSA process using TEM tomography. <i>Proceedings of SPIE</i> , 2015, , .	0.8	6
44	3D TEM Tomography of Templated Bilayer Films of Block Copolymers. <i>Advanced Functional Materials</i> , 2014, 24, 7689-7697.	7.8	22
45	Methods to assess the impact of UV irradiation on the surface chemistry and structure of multiwall carbon nanotube epoxy nanocomposites. <i>Carbon</i> , 2014, 69, 194-205.	5.4	105
46	Dielectric Characterization by Microwave Cavity Perturbation Corrected for Nonuniform Fields. <i>IEEE Transactions on Microwave Theory and Techniques</i> , 2014, 62, 2149-2159.	2.9	43
47	High-speed, high-purity separation of gold nanoparticle-DNA origami constructs using centrifugation. <i>Soft Matter</i> , 2014, 10, 7370.	1.2	29
48	Kilohertz Rotation of Nanorods Propelled by Ultrasound, Traced by Microvortex Advection of Nanoparticles. <i>ACS Nano</i> , 2014, 8, 8300-8309.	7.3	81
49	Resonant Microwave Absorption in Thermally Deposited Au Nanoparticle Films Near Percolation Coverage. <i>Langmuir</i> , 2013, 29, 9010-9015.	1.6	12
50	Quantum dot-DNA origami binding: a single particle, 3D, real-time tracking study. <i>Chemical Communications</i> , 2013, 49, 907-909.	2.2	28
51	Simultaneous positioning and orientation of single nano-wires using flow control. <i>RSC Advances</i> , 2013, 3, 2677.	1.7	27
52	Quantum Dot Fluorescence Lifetime Engineering with DNA Origami Constructs. <i>Angewandte Chemie - International Edition</i> , 2013, 52, 1193-1197.	7.2	71
53	EFTEM Study of a Carbon Nanostructure Composite. <i>Microscopy and Microanalysis</i> , 2012, 18, 1530-1531.	0.2	1
54	DNA evolves. <i>Materials Today</i> , 2012, 15, 526.	8.3	0

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55	Multiple electrokinetic actuators for feedback control of colloidal crystal size. Lab on A Chip, 2012, 12, 4063.	3.1	39
56	Super-resolution Optical Measurement of Nanoscale Photoacid Distribution in Lithographic Materials. ACS Nano, 2012, 6, 9496-9502.	7.3	21
57	Three-Dimensional Real-Time Tracking of Nanoparticles at an Oil-Water Interface. Langmuir, 2012, 28, 9181-9188.	1.6	38
58	Nanomanufacturing with DNA Origami: Factors Affecting the Kinetics and Yield of Quantum Dot Binding. Advanced Functional Materials, 2012, 22, 1015-1023.	7.8	54
59	Lithography, metrology and nanomanufacturing. Nanoscale, 2011, 3, 2679.	2.8	76
60	Ultra-flat coplanar electrodes for controlled electrical contact of molecular films. Review of Scientific Instruments, 2011, 82, 123901.	0.6	7
61	Simultaneous positioning and orientation of a single nano-object by flow control: theory and simulations. New Journal of Physics, 2011, 13, 013027.	1.2	15
62	Spatial coherence in electron-beam patterning. Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics, 2010, 28, 1048-1055.	0.6	5
63	Theoretical model of errors in micromirror-based three-dimensional particle tracking. Optics Letters, 2010, 35, 1905.	1.7	8
64	Measuring the Structure of Epitaxially Assembled Block Copolymer Domains with Soft X-ray Diffraction. Macromolecules, 2010, 43, 433-441.	2.2	40
65	The link between nanoscale feature development in a negative resist and the Hansen solubility sphere. Journal of Polymer Science, Part B: Polymer Physics, 2009, 47, 2091-2105.	2.4	16
66	3D Particle Trajectories Observed by Orthogonal Tracking Microscopy. ACS Nano, 2009, 3, 609-614.	7.3	44
67	The innovator's non-dilemma: the case of next-generation lithography. Managerial and Decision Economics, 2008, 29, 407-423.	1.3	17
68	Fast, bias-free algorithm for tracking single particles with variable size and shape. Optics Express, 2008, 16, 14064.	1.7	59
69	Fabrication and performance of nanoscale ultrasmooth programmed defects for extreme ultraviolet lithography. Journal of Vacuum Science & Technology B, 2008, 26, 6.	1.3	4
70	Soft X-ray Zone Plate Microscopy to 10 nm Resolution with XM-1 at the ALS. AIP Conference Proceedings, 2007, . .	0.3	1
71	Sculpting Semiconductor Heteroepitaxial Islands: From Dots to Rods. Physical Review Letters, 2007, 98, 106102.	2.9	13
72	Size dependent damping in picosecond dynamics of single nanomagnets. Applied Physics Letters, 2007, 90, 202504.	1.5	54

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73	Nanoscale pattern transfer for templates, NEMS, and nano-optics. , 2007, , .		7
74	Design and fabrication of a high-efficiency extreme-ultraviolet binary phase-only computer-generated hologram. Applied Optics, 2007, 46, 2581.	2.1	10
75	Chemical Nanomachining of Silicon by Gold-Catalyzed Oxidation. Nano Letters, 2007, 7, 2009-2013.	4.5	14
76	Programming the Shape of Highly Ordered Ge Islands on Si: from Dots to Rods. AIP Conference Proceedings, 2007, , .	0.3	0
77	Available in print. Nature Nanotechnology, 2007, 2, 533-534.	15.6	2
78	Nano-Scale Imaging With Tabletop Soft X-Ray Lasers: Sub-38 nm Resolution. Springer Proceedings in Physics, 2007, , 417-425.	0.1	1
79	Electrical activation and electron spin coherence of ultralow dose antimony implants in silicon. Applied Physics Letters, 2006, 88, 112101.	1.5	69
80	Magneto-Optical Observation of Picosecond Dynamics of Single Nanomagnets. Nano Letters, 2006, 6, 2939-2944.	4.5	85
81	Bending Soft Block Copolymer Nanostructures by Lithographically Directed Assembly. Macromolecules, 2006, 39, 2435-2437.	2.2	65
82	Tuning Magnetic Domain Structure in Nanoscale La _{0.7} Sr _{0.3} MnO ₃ Islands. Nano Letters, 2006, 6, 1287-1291.	4.5	81
83	Sub-38 nm resolution tabletop microscopy with 13 nm wavelength laser light. Optics Letters, 2006, 31, 1214.	1.7	95
84	New nanofabrication technique using overlay for 15-nm zone plate. , 2006, 6110, 77.		0
85	Soft X-ray microscopy of nanomagnetism. Materials Today, 2006, 9, 26-33.	8.3	104
86	Strategies for integration of donor electron spin qubits in silicon. Microelectronic Engineering, 2006, 83, 1814-1817.	1.1	13
87	Morphological evolution of Ge islands on Au-patterned Si. Journal of Crystal Growth, 2006, 287, 518-521.	0.7	4
88	Fabrication of 30 nm pitch imprint moulds by frequency doubling for nanowire arrays. Nanotechnology, 2006, 17, 4956-4961.	1.3	14
89	Fabrication of 2-dimensional platinum nanocatalyst arrays by electron beam lithography: ethylene hydrogenation and CO-poisoning reaction studies. Topics in Catalysis, 2006, 39, 123-129.	1.3	26
90	Implementation of an imprint damascene process for interconnect fabrication. Journal of Vacuum Science & Technology B, 2006, 24, 1283.	1.3	77

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91	Shot noise models for sequential processes and the role of lateral mixing. Journal of Vacuum Science & Technology B, 2006, 24, 1902.	1.3	21
92	Scanning x-ray microscopy investigations into the electron-beam exposure mechanism of hydrogen silsesquioxane resists. Journal of Vacuum Science & Technology B, 2006, 24, 3048.	1.3	12
93	Ordering and shape tuning of Ge islands on metal-patterned Si. Materials Research Society Symposia Proceedings, 2006, 958, 1.	0.1	0
94	Extreme ultraviolet binary phase gratings: Fabrication and application to diffractive optics. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2006, 24, 1136-1140.	0.9	7
95	Nanometer-scale resolution microscopy with compact extreme ultraviolet lasers. , 2006, , .		0
96	Sub-38 nm resolution microscopy with a tabletop 13 nm wavelength laser. , 2006, , .		1
97	Imaging at High Spatial Resolution: Soft X-Ray Microscopy to 15nm. Journal of Biomedical Nanotechnology, 2006, 2, 75-78.	0.5	16
98	Imaging with sub-38 nm spatial resolution using a tabletop 13 nm wavelength laser. , 2006, , .		0
99	EUV focus sensor: design and modeling. , 2005, , .		0
100	Nano-imaging with compact extreme ultraviolet laser sources. , 2005, , .		0
101	Plasmonic nanorainbow for label-free biomolecule sensing. , 2005, , .		2
102	Nanometer-scale imaging with compact soft x-ray lasers. , 2005, , .		0
103	A dual-mode actinic EUV mask inspection tool. , 2005, 5751, 660.		19
104	Ultra-high accuracy optical testing: creating diffraction-limited short-wavelength optical systems. , 2005, , .		2
105	Advancing the ion beam thin film planarization process for the smoothing of substrate particles. Microelectronic Engineering, 2005, 77, 369-381.	1.1	14
106	Soft X-ray microscopy at a spatial resolution better than 15â€‰nm. Nature, 2005, 435, 1210-1213.	18.7	795
107	10-nm Channel Length Pentacene Transistors. IEEE Transactions on Electron Devices, 2005, 52, 1874-1879.	1.6	94
108	One-kilobit cross-bar molecular memory circuits at 30-nm half-pitch fabricated by nanoimprint lithography. Applied Physics A: Materials Science and Processing, 2005, 80, 1173-1178.	1.1	113

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109	Fabrication of platinum nanoparticles and nanowires by electron beam lithography (EBL) and nanoimprint lithography (NIL): comparison of ethylene hydrogenation kinetics. <i>Catalysis Letters</i> , 2005, 100, 115-124.	1.4	49
110	Ion implantation with scanning probe alignment. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2005, 23, 2798.	1.6	15
111	Directed assembly of Ge islands grown on Au-patterned Si(100). <i>AIP Conference Proceedings</i> , 2005, , .	0.3	0
112	Extreme ultraviolet focus sensor design optimization. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2005, 23, 2885.	1.6	0
113	Profile evolution of Cr masked features undergoing HBr-inductively coupled plasma etching for use in 25- μm silicon nanoimprint templates. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2005, 23, 2073.	1.6	14
114	Metal-Induced Assembly of a Semiconductor Island Lattice: Ge Truncated Pyramids on Au-Patterned Si. <i>Nano Letters</i> , 2005, 5, 2070-2073.	4.5	27
115	Grain Structure in Block Copolymer Thin Films Studied by Guided Wave Depolarized Light Scattering. <i>Macromolecules</i> , 2005, 38, 4282-4288.	2.2	6
116	Cavity-Enhanced Magneto-optical Observation of Magnetization Reversal in Individual Single-Domain Nanomagnets. <i>Nano Letters</i> , 2005, 5, 1413-1417.	4.5	36
117	Integration of Scanning Probes and Ion Beams. <i>Nano Letters</i> , 2005, 5, 1087-1091.	4.5	43
118	Reflection mode imaging with nanoscale resolution using a compact extreme ultraviolet laser. <i>Optics Express</i> , 2005, 13, 3983.	1.7	43
119	Nanoimaging with a compact extreme-ultraviolet laser. <i>Optics Letters</i> , 2005, 30, 2095.	1.7	58
120	Parallel Fabrication of Sub-50-nm Uniformly Sized Nanoparticles by Deposition through a Patterned Silicon Nitride Nanostencil. <i>Nano Letters</i> , 2005, 5, 1129-1134.	4.5	45
121	Fabrication of Metallic Nanodots in Large-Area Arrays by Mold-to-Mold Cross Imprinting (MTMCI). <i>Nano Letters</i> , 2005, 5, 2557-2562.	4.5	37
122	Cross-linked Polymer Replica of a Nanoimprint Mold at 30 nm Half-pitch. <i>Nano Letters</i> , 2005, 5, 179-182.	4.5	70
123	Quantum Computer Development with Single Ion Implantation. , 2005, , 233-245.		2
124	Single ion implantation with scanning probe alignment. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2004, 22, 2992.	1.6	11
125	25- μm mechanically buttressed high aspect ratio zone plates: Fabrication and performance. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2004, 22, 3186.	1.6	24
126	At-wavelength alignment and testing of the 0.3 NA MET optic. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2004, 22, 2956.	1.6	31

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127	Lithographically directed self-assembly of nanostructures. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2004, 22, 3409.	1.6	92
128	Probe shape measurement in an electron beam lithography system. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2004, 22, 2897.	1.6	18
129	Formation of 15-nm scale Coulomb blockade structures in silicon by electron beam lithography with a bilayer resist process. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2004, 22, 3115.	1.6	10
130	Nonaqueous development of silsesquioxane electron beam resist. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2004, 22, 3497.	1.6	28
131	At-Wavelength Interferometry of High-NA Diffraction-Limited EUV Optics. AIP Conference Proceedings, 2004, , .	0.3	3
132	Quantum Computer Development with Single Ion Implantation. Quantum Information Processing, 2004, 3, 233-245.	1.0	17
133	Fabrication of high-efficiency multilayer-coated gratings for the EUV regime using e-beam patterned substrates. Optics Communications, 2004, 229, 109-116.	1.0	20
134	Integration of Colloidal Nanocrystals into Lithographically Patterned Devices. Nano Letters, 2004, 4, 1093-1098.	4.5	507
135	Design, fabrication, and characterization of high-efficiency extreme-ultraviolet diffusers. Applied Optics, 2004, 43, 5323.	2.1	9
136	Status of EUV micro-exposure capabilities at the ALS using the 0.3-NA MET optic. , 2004, 5374, 881.		60
137	EUV interferometric testing and alignment of the 0.3-NA MET optic. , 2004, 5374, 64.		16
138	EUV resist imaging below 50 nm using coherent spatial filtering techniques. , 2004, , .		4
139	Design and fabrication of advanced EUV diffractive elements. , 2004, 5347, 9.		3
140	Scanning Transmission X-ray Microscopes at the Advanced Light Source: Performance and Experimental Capabilities. Microscopy and Microanalysis, 2004, 10, 1018-1019.	0.2	3
141	Solid state quantum computer development in silicon with single ion implantation. Journal of Applied Physics, 2003, 94, 7017-7024.	1.1	97
142	Soft X-ray Microcopy at the ALS. Synchrotron Radiation News, 2003, 16, 16-27.	0.2	3
143	20-nm-resolution Soft x-ray microscopy demonstrated by use of multilayer test structures. Optics Letters, 2003, 28, 2019.	1.7	51
144	20-nm-resolution soft x-ray microscopy demonstrated by use of multilayer test structures: erratum. Optics Letters, 2003, 28, 2530.	1.7	4

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145	Low-cost, low-loss microlens arrays fabricated by soft-lithography replication process. Applied Physics Letters, 2003, 82, 1152-1154.	1.5	145
146	Preparations for extreme ultraviolet interferometry of the 0.3 numerical aperture Micro Exposure Tool optic. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2003, 21, 2706.	1.6	3
147	Nanoscale topography control for the fabrication of advanced diffractive optics. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2003, 21, 2980.	1.6	25
148	EUV interferometry of the 0.3-NA MET optic. , 2003, , .		6
149	X-ray magnetic microscopy for correlations between magnetic domains and crystal structure. European Physical Journal Special Topics, 2003, 104, 477-481.	0.2	2
150	Microlens Arrays for Optoelectronic Devices.. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2002, 15, 497-515.	0.1	8
151	Resist Requirements and Limitations for Nanoscale Electron-Beam Patterning. Materials Research Society Symposia Proceedings, 2002, 739, 151.	0.1	8
152	SCALPEL mask parametric study. , 2001, 4186, 697.		0
153	Space-charge effects in projection electron-beam lithography: Results from the SCALPEL proof-of-lithography system. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2001, 19, 476.	1.6	13
154	Pattern placement correction methodology for 200 mm SCALPEL masks. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2001, 19, 2659.	1.6	0
155	<title>Thermomechanical modeling of the SCALPEL mask during exposure</title>. , 2000, 3997, 549.		1
156	Global space charge effect in SCALPEL. Microelectronic Engineering, 2000, 53, 299-302.	1.1	2
157	Marks for SCALPEL® tool optics optimization. Microelectronic Engineering, 2000, 53, 309-312.	1.1	2
158	Thermal distortion predictions of a silicon wafer during exposure in a SCALPEL tool. Microelectronic Engineering, 2000, 53, 357-360.	1.1	2
159	Critical tool performance analysis for SCALPEL extensibility. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2000, 18, 112.	1.6	1
160	SCALPEL aerial image monitoring: Principles and application to space charge. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2000, 18, 2560.	1.6	3
161	Mechanical and thermal modeling of the SCALPEL mask. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1999, 17, 2878.	1.6	4
162	Thin film stress mapping using an integrated sensor. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1999, 17, 2714.	1.6	5

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163	Finite element analysis of SCALPEL wafer heating. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1999, 17, 2883.	1.6	8
164	Determination of the possible magnitude of the charging effect in a SCALPEL mask membrane. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1999, 17, 2888.	1.6	5
165	SCALPEL mask-membrane charging. Microelectronic Engineering, 1999, 46, 223-226.	1.1	7
166	SCALPEL mask defect imaging analysis. Microelectronic Engineering, 1999, 46, 227-230.	1.1	1
167	Initial wafer heating analysis for a SCALPEL lithography system. Microelectronic Engineering, 1999, 46, 235-238.	1.1	5
168	Optimization of a SCALPEL [®] exposure tool using a diffractive image quality technique. Microelectronic Engineering, 1999, 46, 239-242.	1.1	0
169	Mask membrane distortions due to pattern transfer for electron-beam lithography (SCALPEL) masks. Microelectronic Engineering, 1999, 46, 259-262.	1.1	6
170	Pattern processing results and characteristics for SCALPEL masks. Microelectronic Engineering, 1999, 46, 271-274.	1.1	3
171	Analytical model of the "Shot Noise" effect in photoresist. Microelectronic Engineering, 1999, 46, 365-368.	1.1	5
172	Finite element modeling of SCALPEL masks. , 1999, , .		70
173	Alignment mark detection in CMOS materials with SCALPEL e-beam lithography. , 1999, , .		1
174	Space-charge results from the SCALPEL proof-of-concept system. , 1999, , .		6
175	Modal analysis of the SCALPEL mask using experimental and numerical methods. , 1999, 3676, 556.		2
176	Overview of SCALPEL mask technology. , 1999, , .		0
177	Overlay error budgets for a high-throughput SCALPEL system. , 1999, , .		3
178	Stress mapping techniques for the SCALPEL mask membrane system. , 1999, , .		2
179	<title>SCALPEL mask blank fabrication</title>. , 1999, 3874, 248.		0
180	200-mm SCALPEL mask development. , 1999, , .		4

#	ARTICLE	IF	CITATIONS
181	<title>Modeling of laminar e-beam source for SCALPEL</title>. , 1999, 3777, 60.		0
182	Writing strategy for a high-throughput SCALPEL system. , 1999, 3676, 194.		6
183	Defect inspection and linewidth measurement of SCALPEL thin membrane masks using optical transmission. , 1998, , .		1
184	Dynamic analysis of a SCALPEL mask during electron-beam exposure. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3587.	1.6	6
185	Characterizing GHOST proximity effect correction effectiveness by determining the worst-case error. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3256.	1.6	3
186	Quantitation of latent resist images using photon tunneling microscopy. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3651.	1.6	3
187	Electron scattering and transmission through SCALPEL masks. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3385.	1.6	21
188	Critical dimension control at stitched subfield boundaries in a high-throughput SCALPEL[^{sup} Å [®]] system. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3197.	1.6	4
189	Commercialization of SCALPEL masks. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1998, 16, 3582.	1.6	7
190	Fabrication and commercialization of scalpel masks. , 1998, , .		5
191	Critical issues for developing a high-throughput SCALPEL system for sub-0.18-um lithography generations. , 1998, 3331, 673.		6
192	Equivalent modeling of SCALPEL mask membrane distortions. , 1998, , .		0
193	Mechanical Modeling of Projection Electron-Beam Lithography Masks. Japanese Journal of Applied Physics, 1997, 36, 7564-7569.	0.8	6
194	Metrology of scattering with angular limitation projection electron lithography masks. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1997, 15, 2197.	1.6	4
195	Dose modification proximity effect correction scheme with inherent forward scattering corrections. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1997, 15, 2309.	1.6	17
196	Photon tunneling microscopy of latent resist images. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1997, 15, 2162.	1.6	3
197	Application of transmission electron detection to SCALPEL mask metrology. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1997, 15, 2167.	1.6	7
198	<title>Design of a low-brightness highly uniform source for projection electron-beam lithography (SCALPEL)</title>., 1997, , .		5

#	ARTICLE	IF	CITATIONS
199	SCALPEL proof-of-concept system: preliminary lithography results. , 1997, , .		8
200	Crystallographic aspects of pore formation in gallium arsenide and silicon. Philosophical Magazine A: Physics of Condensed Matter, Structure, Defects and Mechanical Properties, 1997, 75, 525-539.	0.8	32
201	Vacuum ultraviolet rare gas excimer light source. Review of Scientific Instruments, 1997, 68, 1360-1364.	0.6	113
202	The SCALPEL proof of concept system. Microelectronic Engineering, 1997, 35, 477-480.	1.1	12
203	<title>Patterning of membrane masks for projection e-beam lithography</title>. , 1996, , .		0
204	Resist Design Considerations for Direct Write and Projection Electron-Beam Lithography Technologies.. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 1996, 9, 663-675.	0.1	6
205	Preliminary results from a prototype projection electron-beam stepper-scattering with angular limitation projection electron beam lithography proof-of-concept system. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1996, 14, 3825.	1.6	17
206	<title>Stochastic interactions in particle-projection systems: comparison of theory and Monte Carlo simulations</title>. , 1995, , .		1
207	<title>Fabrication processes for SCALPEL mask blanks</title>. , 1995, 2621, 247.		0
208	Stochastic scattering in charged particle projection systems: A nearest neighbor approach. Journal of Applied Physics, 1995, 78, 6888-6902.	1.1	41
209	Space charge effects in projection charged particle lithography systems. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1995, 13, 2404.	1.6	25
210	Lithographic evaluation of a positive-acting chemically amplified resist system under conventional and projection electron-beam exposures. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1995, 13, 2975.	1.6	1
211	Error budget analysis of the SCALPEL(R) mask for sub-0.2 Î¼m lithography. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1995, 13, 2483.	1.6	10
212	A background dose proximity effect correction technique for scattering with angular limitation projection electron lithography implemented in hardware. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1995, 13, 2504.	1.6	12
213	The SScattering with Angular Limitation in Projection Electron-Beam Lithography (SCALPEL) System. Japanese Journal of Applied Physics, 1995, 34, 6663-6671.	0.8	19
214	Proximity Effect Correction in Projection Electron Beam Lithography (Scattering with Angular) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 50 147 6672-6678.	0.8	6
215	Fracture Strength of Thin Ceramic Membranes. Materials Research Society Symposia Proceedings, 1994, 338, 501.	0.1	9
216	Lithographic performance of a negative resist under scattering with angular limitation for projection electron lithography exposure at 100 keV. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 3444.	1.6	1

#	ARTICLE	IF	CITATIONS
217	An analytical model of stochastic interaction effects in projection systems using a nearest-neighbor approach. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 3508.	1.6	18
218	Stress-induced pattern-placement errors in thin membrane masks. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 3528.	1.6	7
219	Absorption and luminescence studies of free-standing porous silicon films. Physical Review B, 1994, 49, 5386-5397.	1.1	106
220	<title>SCALPEL system</title>. , 1994, , .		8
221	<title>SCALPEL masks</title>. , 1994, , .		2
222	Alignment mark materials for projection electron lithography. Proceedings Annual Meeting Electron Microscopy Society of America, 1994, 52, 712-713.	0.0	0
223	Transport in submicrometer buried mesotaxial cobalt silicide wires. Applied Physics Letters, 1993, 62, 387-389.	1.5	22
224	<title>High-throughput projection electron-beam lithography employing SCALPEL</title>. , 1993, , .		1
225	Choice of system parameters for projection electron-beam lithography: Accelerating voltage and demagnification factor. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1992, 10, 2776.	1.6	11
226	Mark detection for alignment and registration in a high-throughput projection electron lithography tool. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1992, 10, 2780.	1.6	6
227	Ultra-high-resolution chemical analysis by field-ion microscopy, atom probe and position-sensitive atom-probe techniques. Ultramicroscopy, 1992, 47, 199-211.	0.8	2
228	Ultrahigh resolution characterisation of compound semiconductors using pulsed laser atom probe techniques. Applied Surface Science, 1991, 50, 196-201.	3.1	3
229	Projection electron-beam lithography: A new approach. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1991, 9, 2996.	1.6	66
230	Compositional homogeneity of metalorganic chemical vapor deposition grown III-V compound semiconductor epilayers. Journal of Applied Physics, 1991, 69, 250-256.	1.1	16
231	Mask fabrication for projection electron-beam lithography incorporating the SCALPEL technique. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1991, 9, 3000.	1.6	20
232	Application of position sensitive atom probe to the study of the microchemistry and morphology of quantum well interfaces. Applied Physics Letters, 1989, 54, 1555-1557.	1.5	12
233	Materials analysis with a position-sensitive atom probe. Journal of Microscopy, 1989, 154, 215-225.	0.8	53
234	PULSED LASER ATOM PROBE ANALYSIS OF TERNARY AND QUATERNARY III-V EPITAXIAL LAYERS. Journal De Physique Colloque, 1988, 49, C6-509-C6-514.	0.2	18

#	ARTICLE	IF	CITATIONS
235	ALLOY CARBIDE PRECIPITATION IN A HIGH COBALT-NICKEL SECONDARY HARDENING STEEL. Journal De Physique Colloque, 1986, 47, C7-223-C7-231.	0.2	6